

ABSTRACT

An apparatus, for measuring overlay, includes: a height difference detection optical system detecting a height difference between a first overlay mark and a second overlay mark; an illumination optical system irradiating the overlay mark with illumination light; a main beam splitter splitting a reflected light from the overlay mark into a first beam and a second beam; a first detector receiving the first beam and generating a first overlay mark image in which the first overlay mark is displayed; a second detector receiving the second beam and generating a second overlay mark image in which the second overlay mark is displayed; an imaging optical system allowing the first beam to be imaged on the first detector; and a telecentric imaging optical system adjusting a length of an optical path of the second beam to allow the second beam to be imaged on the second detector.

[Figure 5]